	Application No.	Applicant(s)	
Notice of Allowability	10/092 200		
	10/082,399 Examiner	FEDYNYSHYN, THEODOR	<u>E H.</u>
		Artonic	
	John S. Chu	1752	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313) OR REMAINS) CLOSED) or other appropriate communication in	in this application. If not included	THIS initiative
1. This communication is responsive to <u>10/22/04</u> .			
2. The allowed claim(s) is/are <u>1 and 3-27</u> .			
3. The drawings filed on are accepted by the Examine			
4. ☐ Acknowledgment is made of a claim for foreign priority un a) ☐ All b) ☐ Some* c) ☐ None of the:		or (f).	
 Certified copies of the priority documents have 	e been received.		
2. Certified copies of the priority documents have	been received in Applicati	on No.	
3. Copies of the certified copies of the priority do	cuments have been receive	ed in this national stage application from	tho
international Bureau (PCT Rule 17.2(a)).	. *	The state of the s	uie
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to fil IENT of this application.	e a reply complying with the requirement	ts
5. A SUBSTITUTE OATH OR DECLARATION must be subminFORMAL PATENT APPLICATION (PTO-152) which give	itted. Note the attached EX es reason(s) why the oath o	AMINER'S AMENDMENT or NOTICE Or declaration is deficient.)F
6. CORRECTED DRAWINGS (as "replacement sheets") mus	t be submitted.		
(a) including changes required by the Notice of Draftspers	on's Patent Drawing Revie	w (PTO-948) attached	
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date		(v v v v v v v v v v v v v v v v v v v	
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	Amendment / Comment o	r in the Office action of	
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the	84(c)) should be written on t	he drawings in the front (not the back) of	
7. DEPOSIT OF and/or INFORMATION about the depose attached Examiner's comment regarding REQUIREMENT F	sit of BIOLOGICAL MAT	ERIAL must be submitted at a a	
Attack was a t/a \			
Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5 □ N # - 6:		
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)		formal Patent Application (PTO-152)	
	Danar Na /	ummary (PTO-413), Mail Date	
 Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No./Mail Date 	3), 7. Examiner's	Amendment/Comment	
4. Examiner's Comment Regarding Requirement for Deposit	8. Examiner's	Statement of Reasons for Allowance	
of Biological Material	9. 🗌 Other		
f			
			1

Application/Control Number: 10/082,399

Art Unit: 1752

REASONS FOR ALLOWANCE

1. The following is an examiner's statement of reasons for allowance: The claimed invention is drawn to the following:

1.(Currently Amended) A photoresist composition, comprising a resin binder, and

an encapsulated material comprising inorganic core particles at least partially coated with a moiety having a protected acidic group, said coated particles being distributed within the resin,

wherein the protected acidic group comprises an acid labile group.

17. (Currently Amended) A method of processing a semiconductor substrate, comprising:

coating the substrate surface with a photoresist composition comprising a resin binder, and an encapsulated material comprising inorganic core particles at least partially coated with a moiety having a protected acidic group selected from the group consisting of an acid-labile group and a photo-labile group, said coated particles being dispersed within said resin binder,

exposing selected portions of the coated surface to an activating radiation to cause a chemical transformation in the exposed portions,

removing either the radiation-exposed or unexposed portions of the photoresist composition, and

plasma-etching the substrate surface to generate a pattern thereon.

Applicants have amended the claims in accordance with the suggestions by the examiner as indicated in the Office action mailed July 14, 2004, paragraph 3. The recitation of an acid-labile and/or photolabile group partially coated on an inorganic core particle is not suggested or disclosed in the prior art references of record nor is the method of processing a substrate having a photoresist composition as recited.

The rejection over NAGASHIMA et al under 35 U.S.C. 102(b) is overcome by the amendments above and is withdrawn.

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Because none of the references of record anticipate or render obvious the claimed invention, claims 1, 3-27 are seen as allowable and passed to issue.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

2. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

The fax phone number for the USPTO is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the Group receptionist whose telephone number is (571) 272-1700.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PMR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

John S. Chu

Primary Examiner, Group 1700

J.Chu December 10, 2004